

## **PATENT**

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Serial No.:

10/800,219

Filed:

March 12, 2004

Title:

Method and Apparatus for Verifying )

the Post-Optical Proximity Corrected)
Mask Wafer Image Sensitivity to

Reticle Manufacturing Errors

Inventors:

Nadya G. Strelkova et al.

Art Unit:

2825

Examiner:

Nelson C. Lam

Atty. Ref:

02-2396

## CERTIFICATE OF MAILING

I hereby certify that this paper is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on October 2, 2008.

James R. Foley, Reg. No. 893

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RESPONSE TO THE OFFICE ACTION MAILED JULY 31, 2006

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In the matter of the above-identified application and in response to the Office Action mailed July 31, 2006, kindly enter the following amendments and consider the following remarks toward reconsideration of the present application.